
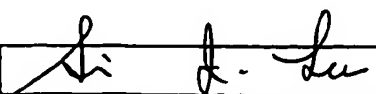


Substitute form 1449A/PTO					<b>Complete if Known</b>	
<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (use as many sheets as necessary)			Application Number		10/800,195	
			Filing Date		03/12/04	
			First Named Inventor		Dai	
			Group Art Unit		1752	
			Examiner Name		Unknown	
Sheet	A1	of	A1	Attorney Docket Number		5347-218

U.S. PATENTS AND PATENT PUBLICATIONS					
Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Number	Kind Code (if known)		
SJL ↓	1.	US-6482566		Hofer et al.	11192002
	2.	US-6492259		Dirahoui et al.	12102002

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Office	Number	Kind Code (if known)		

OTHER NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published		
SJL	3.	Dai et al. "Organoelement resists for EUV lithography," SPIE The International Society for Optical Engineering 4690:1193-1202 (2002)		

Examiner Signature		Date Considered	4-3-05
--------------------	---	-----------------	--------

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.